

IN THE CLAIMS

1 (Currently Amended). A method comprising:

forming a photoresist by attaching a photoactive compound including diazonaphthoquinone to a polymer backbone; and
exposing said photoresist to extreme ultraviolet radiation.

2 (Original). The method of claim 1 including attaching diazonaphthoquinone as the photoactive compound.

3 (Original). The method of claim 2 including attaching hydroxystyrene groups to said backbone.

4 (Original). The method of claim 3 including attaching a first moiety to one hydroxystyrene group and a second moiety, different from said first moiety, to a second hydroxystyrene group.

5 (Original). The method of claim 4 including selecting said moieties from hydrogen, hydroxyl, and alkyl.

6 (Original). The method of claim 1 including using from 10 to 20% of diazonaphthoquinone on a molar basis.

7 (Original). The method of claim 2 including forming non-reactive compounds upon exposure to radiation.

8 (Original). The method of claim 4 including forming nitrogen upon irradiation.

Claims 9-20 (Canceled).